

OCT 13 2005

OMB No. 0651-0011

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INFORMATION DISCLOSURE STATEMENT	Atty. Docket No.: 150.01100101	Serial No.: 10/028,616
	Applicant(s): Sabde	Confirmation No.: 6755
	Application Filing Date: December 21, 2001	Group: 3723
	Information Disclosure Statement mailed: <u>July 27</u> , 2004	

U.S. PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
SLM	X	US 2003/0166337 A1	09/04/03	Wang et al.			

FOREIGN PATENT DOCUMENTS

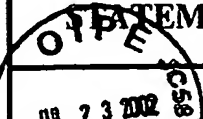
Examiner Initial	Copy Enclosed	Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No

OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)

Examiner Initial	Copy Enclosed	Document Description

EXAMINER <i>Shawna de la Cruz</i>	Date Considered <u>10/19/05</u>
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INFORMATION DISCLOSURE STATEMENT 	Atty. Docket No.: 150.01100101	Sérial No.: 10/028,616
	Applicants: Gundu M. Sabde	Confirmation No.: 6755
	Filing Date: December 21, 2001	Group: 3723
	Information Disclosure Statement mailed: July <u>19</u> , 2002	

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
SLM	4,992,137	02/12/91	Cathey, Jr. et al.			
	5,254,217	10/19/93	Maniar et al.			
	5,380,401	01/10/95	Jones et al.			
	5,392,189	02/21/95	Fazan et al.			
	5,575,885	11/19/96	Hirabayashi et al.			
	5,692,950	12/02/97	Rutherford et al.			
	5,711,851	01/27/98	Blalock et al.			
	5,786,259	07/28/98	Kang			
	5,888,906	03/30/99	Sandhu et al.			
	5,916,855	06/29/99	Avanzino et al.			
	5,954,997	09/21/99	Kaufman et al.			
	5,976,928	11/02/99	Kirlin et al.			
	5,981,454	11/09/99	Small			
	5,989,988	11/23/99	Iinuma et al.			
	6,039,633	03/21/00	Chopra			
	6,045,716	04/04/00	Walsh et al.			
	6,071,816	06/06/00	Watts et al.			
	6,143,191	11/07/00	Baum et al.			
	6,149,828	11/21/00	Vaartstra			
	6,211,034	04/03/01	Visokay et al.			
	6,290,736 B1	09/18/01	Evans			
	6,346,741 B1	02/12/02	Van Buskirk et al.			
	6,368,518	04/09/02	Vaartstra			
SLM	6,395,194 B1	05/28/02	Russell et al.			

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Shantese McDonald

Date Considered

1/26/03

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	Applicants: Gundu M. Sabde	Confirmation No.: 6755
	Filing Date: December 21, 2001	Group: 3723
	Information Disclosure Statement mailed: July 19, 2002	

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
SL	WO 98/06541	02/19/98	PCT				
	WO 98/36045	08/20/98	PCT				
	WO 99/27581	06/03/99	PCT				
	WO 99/53532	10/21/99	PCT				
SL	WO 00/31794	06/02/00	PCT				

OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)

Examiner Initial	Document Description
SL	Canterford et al., "Chapter 9: Rhodium and Iridium," <i>Halides of the Transition Elements, Halides of the Second and Third Row Transition Metals</i> , John Wiley & Sons, New York, NY, 1968; pgs. 346-357, publication page, title page (14 pages total).
	DeOrnellas et al., "Challenges for Plasma Etch Integration of Ferroelectric Capacitors in FeRAM's and DRAM's," <i>Integrated Ferroelectrics</i> , 1997;17:395-402.
	DeOrnellas et al., "Plasma Etch of Ferroelectric Capacitors in FeRAMs and DRAMs," <i>Semiconductor International</i> , 1997 Sept.; pgs. 103-104, 106 and 108.
	Ginzburg et al., <i>Analytical Chemistry of Platinum Metals</i> , John Wiley & Sons, New York, cover pg., and 14-15.
	Kim et al., "Chemical Dry Etching of Platinum Using Cl ₂ /CO Gas Mixture," <i>Chem. Mater.</i> , 1998;10:3576-3582.
	Kwon et al., "Etching properties of Pt thin films by inductively coupled plasma," <i>J. Vac. Sci. Technol.</i> , 1998;A 16(5):2772-6.
	Nakao, "Dissolution of Noble Metals in Halogen-Halide-Polar Organic Solvent Systems," <i>J. Chem. Soc., Chem. Commun.</i> , 1992 March 1; 5:426-7.
SL	Wilberg, <i>Lehrbuch der Anorganischen Chemie</i> , Walter de Gruyter, Berlin, 1985, Cover pg., and 1188.

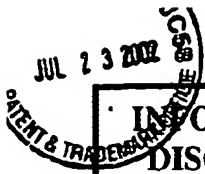
EXAMINER

Sherrin McDonald

Date Considered

11/22/03

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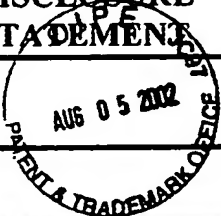


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	Applicants: Gundu M. Sabde	Confirmation No.: 6755
	Filing Date: December 21, 2001	Group: 3723
Information Disclosure Statement mailed: July <u>19</u> , 2002		

Examiner Initial	Document Description
Sum	Xu et al., "Chemical Vapor Deposition (CVD) of Iridium and Platinum Films and Gas-Phase Chemical Etching of Iridium Thin Films," <i>Mat. Res. Soc. Symp. Proc.</i> , 1999;541:129-139.

EXAMINER Shantee McDonald	Date Considered 11/22/03
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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT	Atty. Docket No.: 150.01100101	Serial No.: 10/028,616
	Applicants: Gundu M. Sabde	Confirmation No.: 6755
	Filing Date: December 21, 2001	Group: 3723
Supplemental Information Disclosure Statement mailed: July <u>31</u> , 2002		

**U.S. PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	None					

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	None						

OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)

Examiner Initial	Document Description
SLM	Wilberg, "Chapter XXX, No. 4: Chemical Properties," <i>Lehrbuch der Anorganischen Chemie</i> , Walter de Gruyter, Berlin, 1985, p. 1118 (Translation of First paragraph only).

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EXAMINER <i>Shawles, Nelson</i>	Date Considered <i>1/26/03</i>
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